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## **OAI's Nano Imprint Lithography Module (NIL) & Backside Mask Aligner chosen by FLORIDA INTERNATIONAL UNIVERSITY**

January 6, 2009, San Jose, CA: **OAI**, a leading manufacturer of UV exposure equipment for Semiconductor, MEMS, Microfluidics, and Nanotechnology, announces that Florida International University (FIU) chose OAI's Model 800 front and backside mask aligner with OAI's Nano Imprint Module (NIL). The Nano Imprint used on the OAI mask aligner was developed at HP Labs. Through a technology agreement, OAI offers the imprint module and the high yield release technology that came from research at the HP Labs.

"We are pleased that FIU will utilize OAI's advanced NIL Technology in their research and teaching programs," said Dr. Charles Turk, President of OAI. "The use of the imprint module with the Model 800 Mask Aligner provides a flexible platform for advanced semiconductor lithography, MEM's, as well as Nano Imprinting. The change over from lithography to nano imprinting can be accomplished in less than 15 minutes. FIU selected the OAI system because of its proven technology and budget friendly pricing", he added. The system is scheduled for installation the first quarter of 2009.

OAI's Nano Imprint Module can be added to any mask aligner. The NIL package comes complete with aligner module, imprint materials, test mold and training.

**OAI** is a leading manufacturer of precision equipment used in the Semiconductor, MEMS, and Nanotechnology Industries for over 30 years. Located in Silicon Valley, **OAI** can be contacted via e. mail:

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